

ABSTRACT

A lithographic projection apparatus includes a radiation system for providing a beam of radiation and a support structure for supporting a patterning device. The patterning device serves to pattern the beam according to a desired pattern. The lithographic projection apparatus includes a substrate table for holding a substrate and a projection system for projecting the patterned beam onto a target portion of the substrate. At least one holding structure includes at least one compliant member holding a pimple plate for holding a removable item for the apparatus.